ABSTRACT

ASYMMETRIC PATTERN PROJECTION APPARATUS

An apparatus for inspection of a surface of a device comprises a projection module operative to project a pattern along a projection axis of the projection module onto the device. An imaging module receives an image of the pattern reflected from the device along an imaging axis of the imaging module onto an image sensor. A lens comprised in the imaging module has a first magnification in a first direction orthogonal to the imaging axis and a second magnification different from the first magnification in a second direction orthogonal to both the first direction and the imaging axis, which produces different fields of view of the image sensor and resolutions of the image in the first and second directions.

(FIG. 5)